



GAU 3723/15

#61 8/8/01  
V. Hart

PATENT

Attorney Docket No.: 29273/516

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Inventor : Shigeo MORIYAMA, et al.  
Serial No. : 09/462,912  
Filed : October 28, 1998  
For : POLISHING APPARATUS AND METHOD FOR PRODUCING SEMICONDUCTORS USING THE APPARATUS  
Group Art Unit : 3723

Assistant Commissioner for Patents  
Washington D.C. 20231

**RESPONSE TO OFFICE ACTION**

S I R:

In response to the Office Action dated March 13, 2001, the due date being extended by the attached Petition for Extension of Time, please amend the application as follows:

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**IN THE CLAIMS:**

Please amend claims 1, 5, 10 and 11 as follows:

1. (Amended) A polishing apparatus which imparts relative motion between a layer with a concave portion and a convex portion on a semiconductor wafer and a polishing tool to polish the surface of said workpiece by a polishing surface of said polishing tool, comprising:
- a dressing tool for forming a surface roughness on the polishing surface of said polishing tool;

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